Ref #	Hits	Search Query	DBs	Default Operator	Plurals	Time Stamp
S1	4	(("6170492") or ("6635117")).PN.	US-PGPUB; USPAT; USOCR; EPO; JPO; DERWENT; IBM_TDB	OR	OFF	2005/03/14 08:50
S2	2	"6635117" and (clean or cleaning or remove or removing or removed)	USPAT	OR	ON	2005/03/14 08:55
S3	159	("cvd" or "chemical vapor deposition") and (fluorine near10 (gas or vapor or atmosphere or environment)) and ((shower or sprinkler or nozzle or jet or sprayer or spout) near10 (heated or heater or hot))	US-PGPUB; USPAT; USOCR; EPO; JPO; DERWENT; IBM_TDB	OR	ON	2005/03/14 09:18
S4	159	("cvd" or "chemical vapor deposition") and ((fluorine or flouride) near10 (gas or vapor or atmosphere or environment)) and ((shower or sprinkler or nozzle or jet or sprayer or spout) near10 (heated or heater or hot))	US-PGPUB; USPAT; USOCR; EPO; JPO; DERWENT; IBM_TDB	OR	ON	2005/03/14 09:19
S5	188	("cvd" or "chemical vapor deposition") and ((fluorine or fluoride) near10 (gas or vapor or atmosphere or environment)) and ((shower or sprinkler or nozzle or jet or sprayer or spout) near10 (heated or heater or hot))	US-PGPUB; USPAT; USOCR; EPO; JPO; DERWENT; IBM_TDB	OR	ON	2005/03/14 10:04
S6	2	("cvd" or "chemical vapor deposition") and ((fluorine or fluoride) near10 (gas or vapor or atmosphere or environment) near15 microwave) and ((shower or sprinkler or nozzle or jet or sprayer or spout) near10 (heated or heater or hot))	US-PGPUB; USPAT; USOCR; EPO; JPO; DERWENT; IBM_TDB	OR	ON	2005/03/14 09:35
S7	3	("cvd" or "chemical vapor deposition") and ((fluori$7) near10 (gas or vapor or atmosphere or environment) near15 microwave) and ((shower or sprinkler or nozzle or jet or sprayer or spout) near10 (heated or heater or hot))	US-PGPUB; USPAT; USOCR; EPO; JPO; DERWENT; IBM_TDB	OR	ON	2005/03/14 09:37

S8	207	("cvd" or "chemical vapor deposition") and ((fluori$7) near10 (gas or vapor or atmosphere or environment) near15 microwave)	US-PGPUB; USPAT; USOCR; EPO; JPO; DERWENT; IBM_TDB	OR	ON	2005/03/14 09:37
S9	161	("cvd" or "chemical vapor deposition") and ((fluori$7) near10 (gas or vapor or atmosphere or environment) near15 microwave) and ((wafer or substrate or semiconductor or workpiece) near10 (clean or cleaning or cleaned))	US-PGPUB; USPAT; USOCR; EPO; JPO; DERWENT; IBM_TDB	OR	ON	2005/03/14 09:39
S10	161	("cvd" or "chemical vapor deposition") and ((fluori$7) near10 (gas or vapor or atmosphere or environment or excited or excitation) near15 microwave) and ((wafer or substrate or semiconductor or workpiece) near10 (clean or cleaning or cleaned))	US-PGPUB; USPAT; USOCR; EPO; JPO; DERWENT; IBM_TDB	OR	ON	2005/03/14 09:39
S11	1	("cvd" or "chemical vapor deposition") and ((fluorine or fluoride) near10 (gas or vapor or atmosphere or environment) near15 (microwave or excited or excitation))) and ((shower or sprinkler or nozzle or jet or sprayer or spout) near15 ((heated or heater or hot) near15 (raised or increas$7 or vary or varied or varying or changed or lowered or decreas$7))	US-PGPUB; USPAT; USOCR; EPO; JPO; DERWENT; IBM_TDB	OR	ON	2005/03/14 10:09
S12	1	("cvd" or "chemical vapor deposition") and ((fluoride or fluorine or fluorous) near10 (gas or vapor or atmosphere or environment) near15 (microwave or excited or excitation))) and ((shower or sprinkler or nozzle or jet or sprayer or spout) near15 ((heated or heater or hot) near15 (raised or increas$7 or vary or varied or varying or changed or lowered or decreas$7))	US-PGPUB; USPAT; USOCR; EPO; JPO; DERWENT; IBM_TDB	OR	ON	2005/03/14 10:13

S13	1	("cvd" or "chemical vapor deposition" or "156"/$.ccls. or "216"/$.ccls. or "134"/$.ccls.) and ((fluoride or fluorine or fluorous) near10 (gas or vapor or atmosphere or environment) near15 (microwave or excited or excitation))) and ((shower or sprinkler or nozzle or jet or sprayer or spout) near15 ((heated or heater or hot) near15 (raised or increas$7 or vary or varied or varying or changed or lowered or decreas$7))	US-PGPUB; USPAT; USOCR; EPO; JPO; DERWENT; IBM_TDB	OR	ON	2005/03/14 10:15
S14	4353	((shower or sprinkler or nozzle or jet or sprayer or spout) near15 ((heated or heater or hot) near15 (raised or increas$7 or vary or varied or varying or changed or lowered or decreas$7)))	US-PGPUB; USPAT; USOCR; EPO; JPO; DERWENT; IBM_TDB	OR	ON	2005/03/14 10:15
S15	279	((shower or sprinkler or nozzle or jet or sprayer or spout) near15 ((heated or heater or hot) near15 (raised or increas$7 or vary or varied or varying or changed or lowered or decreas$7))) and ("cvd" or "chemical vapor deposition" or "156"/$.ccls. or "216"/$.ccls. or "134"/$.ccls.)	US-PGPUB; USPAT; USOCR; EPO; JPO; DERWENT; IBM_TDB	OR	ON	2005/03/14 10:18
S16	181	((shower or sprinkler or nozzle or jet or sprayer or spout) near15 ((heated or heater or hot) near15 (raised or increas$7 or vary or varied or varying or changed or lowered or decreas$7))) and ("cvd" or "chemical vapor deposition" or "156"/$.ccls. or "216"/$.ccls. or "134"/$.ccls.) and (wafer or substrate or semiconductor or workpiece)	US-PGPUB; USPAT; USOCR; EPO; JPO; DERWENT; IBM_TDB	OR	ON	2005/03/14 11:48
S17	59	((("cvd" or "chemical vapor deposition") near10 chamber) near15 (clean or cleaning or cleaned)) and ((shower or sprinkler or nozzle or jet or sprayer or spout) near15 (heated or heater or hot or heating or heat))	US-PGPUB; USPAT; USOCR; EPO; JPO; DERWENT; IBM_TDB	OR	ON	2005/03/14 12:11

S18	60	((("cvd" or "chemical vapor deposition") near10 chamber) near15 (clean or cleaning or cleaned or decontaminat$7)) and ((shower or sprinkler or nozzle or jet or sprayer or spout) near15 (heated or heater or hot or heating or heat))	US-PGPUB; USPAT; USOCR; EPO; JPO; DERWENT; IBM_TDB	OR	ON	2005/03/14 12:13
S19	120	((("cvd" or "chemical vapor deposition" or plasma) near10 chamber) near15 (clean or cleaning or cleaned or decontaminat$7)) and ((shower or sprinkler or nozzle or jet or sprayer or spout) near15 (heated or heater or hot or heating or heat))	US-PGPUB; USPAT; USOCR; EPO; JPO; DERWENT; IBM_TDB	OR	ON	2005/03/14 13:32
S20	7530	manos	US-PGPUB; USPAT; USOCR; EPO; JPO; DERWENT; IBM_TDB	OR	ON	2005/03/14 12:31
S21	5	"5672764"	US-PGPUB; USPAT; USOCR; EPO; JPO; DERWENT; IBM_TDB	OR	ON	2005/03/14 12:32
S22	34	"5672212"	US-PGPUB; USPAT; USOCR; EPO; JPO; DERWENT; IBM_TDB	OR	ON	2005/03/14 13:06
S23	17	"5709757" and "c"	US-PGPUB; USPAT; USOCR; EPO; JPO; DERWENT; IBM_TDB	OR	ON	2005/03/14 13:06
S24	135	((("cvd" or "chemical vapor deposition" or plasma) near10 (chamber or reactor)) near15 (clean or cleaning or cleaned or decontaminat$7)) and ((shower or sprinkler or nozzle or jet or sprayer or spout) near15 (heated or heater or hot or heating or heat))	US-PGPUB; USPAT; USOCR; EPO; JPO; DERWENT; IBM_TDB	OR	ON	2005/03/16 06:42

S25	72	(("cvd" or "chemical vapor deposition" or plasma) near10 (chamber or reactor)) and ((layer or film) near20 (working or production or formation or formed) near29 (temperature or "C" or "F")) and ((clean or cleaned or cleaning) near20 (temperature or "C" or "F")) and ((shower or sprinkler or nozzle or jet or sprayer or spout) near15 (heated or heater or hot or heating or heat))	US-PGPUB; USPAT; USOCR; EPO; JPO; DERWENT; IBM_TDB	OR	ON	2005/03/16 08:16
S26	77	(("cvd" or "chemical vapor deposition" or plasma) near10 (chamber or reactor)) and ((layer or film) near20 (fabricat$7 or process or processing) near29 (temperature or "C" or "F")) and ((clean or cleaned or cleaning) near20 (temperature or "C" or "F")) and ((shower or sprinkler or nozzle or jet or sprayer or spout) near15 (heated or heater or hot or heating or heat))	US-PGPUB; USPAT; USOCR; EPO; JPO; DERWENT; IBM_TDB	OR	ON	2005/03/16 08:18
S27	72	(("cvd" or "chemical vapor deposition" or plasma) near10 (chamber or reactor)) and ((layer or film) near20 (working or production or formation or formed) near29 (temperature or "C" or "F")) and ((clean or cleaned or cleaning) near20 (temperature or "C" or "F")) and ((shower or sprinkler or nozzle or jet or sprayer or spout) near15 (heated or heater or hot or heating or heat))	US-PGPUB; USPAT; USOCR; EPO; JPO; DERWENT; IBM_TDB	OR	ON	2005/03/16 08:39
S28	36	S26 not S27	US-PGPUB; USPAT; USOCR; EPO; JPO; DERWENT; IBM_TDB	OR	ON	2005/03/16 08:18

S29	1598	(("cvd" or "chemical vapor deposition" or plasma or (chemical near5 vapor near5 deposition)) near10 (chamber or reactor)) and ((layer or film) near15 (fabricat$7 or process or processing or working or production or formation or formed) near20 (temperature or "C" or "F")) and ((clean or cleaned or cleaning) near20 (temperature or "C" or "F"))	US-PGPUB; USPAT; USOCR; EPO; JPO; DERWENT; IBM_TDB	OR	ON	2005/03/16 08:43
S30	1463	(("cvd" or "chemical vapor deposition" or plasma or (chemical near5 vapor near5 deposition)) near10 (chamber or reactor)) and ((layer or film) near15 (fabricat$7 or process or processing or working or production or formation or formed) near15 (temperature or "C" or "F")) and ((clean or cleaned or cleaning) near15 (temperature or "C" or "F"))	US-PGPUB; USPAT; USOCR; EPO; JPO; DERWENT; IBM_TDB	OR	ON	2005/03/16 08:43
S31	1293	(("cvd" or "chemical vapor deposition" or plasma or (chemical near5 vapor near5 deposition)) near5 (chamber or reactor)) and ((layer or film) near15 (fabricat$7 or process or processing or working or production or formation or formed) near15 (temperature or "C" or "F")) and ((clean or cleaned or cleaning) near15 (temperature or "C" or "F"))	US-PGPUB; USPAT; USOCR; EPO; JPO; DERWENT; IBM_TDB	OR	ON	2005/03/16 08:44
S32	489	(("cvd" or "chemical vapor deposition" or plasma or (chemical near5 vapor near5 deposition)) near5 (chamber or reactor)) and ((layer or film) near15 (fabricat$7 or process or processing or working or production or formation or formed) near15 (temperature or "C" or "F")) and ((chamber or reactor) near15 (clean or cleaned or cleaning) near15 (temperature or "C" or "F"))	US-PGPUB; USPAT; USOCR; EPO; JPO; DERWENT; IBM_TDB	OR	ON	2005/03/16 08:58

S33	523	(("cvd" or "chemical vapor deposition" or plasma or (chemical near5 vapor near5 deposition)) near5 (chamber or reactor)) and ((layer or film) near15 (fabricat$7 or process or processing or working or production or formation or formed or forming) near15 (temperature or "C" or "F")) and ((chamber or reactor) near15 (clean or cleaned or cleaning) near15 (temperature or "C" or "F"))	US-PGPUB; USPAT; USOCR; EPO; JPO; DERWENT; IBM_TDB	OR	ON	2005/03/16 09:09
S34	335	(("cvd" or "chemical vapor deposition" or plasma or (chemical near5 vapor near5 deposition)) near5 (chamber or reactor)) and ((layer or film) near15 (fabricat$7 or process or processing or working or production or formation or formed or forming) near15 (temperature)) and ((chamber or reactor) near15 (clean or cleaned or cleaning) near15 (temperature))	US-PGPUB; USPAT; USOCR; EPO; JPO; DERWENT; IBM_TDB	OR	ON	2005/03/16 09:51
S35	10	"2183204"	EPO; JPO; DERWENT; IBM_TDB	OR	ON	2005/03/16 11:22
S36	3	"5647945" and microwave	USPAT	OR	ON	2005/03/18 06:37
S37	0	"6576481" and (microwave or magnetron)	USPAT	OR	ON	2005/03/18 06:37
S38	1	"6576481" and (microwave or magnetron silicon or tungsten)	USPAT	OR	ON	2005/03/18 08:27
S39	1	"6841203" and (clean$5)	USPAT	OR	ON	2005/03/18 08:09
S40	2	("6177149").PN.	US-PGPUB; USPAT; USOCR; EPO; JPO; DERWENT; IBM_TDB	OR	OFF	2005/03/18 08:01
S41	2	"6177149" and (clean$5)	USPAT	OR	ON	2005/03/18 08:03
S42	3	"6444042" and (clean$5)	USPAT	OR	ON	2005/03/18 08:10
S43	45	"5616208" and (clean$5)	USPAT	OR	ON	2005/03/18 08:12
S44	50	"5616208" and (clean$5 or chamber or reactor)	USPAT	OR	ON	2005/03/18 08:13
S45	1	"6576481" and (microwave or magnetron silicon or tungsten)	USPAT	OR	ON	2005/03/18 08:31
S46	14	"5647945" and (microwave or magnetron silicon or tungsten)	USPAT	OR	ON	2005/03/18 15:52

S47	1	"6645303" and (microwave or magnetron silicon or tungsten)	USPAT	OR	ON	2005/03/18 08:44
S48	1	"6645303" and (tungsten)	USPAT	OR	ON	2005/03/18 08:52
S49	3	"5161208" and (microwave or magnetron silicon or tungsten)	USPAT	OR	ON	2005/03/18 08:45
S50	39	"5616208" and (microwave or magnetron silicon or tungsten)	USPAT	OR	ON	2005/03/18 08:48
S51	39	"5616208" and (microwave or magnetron silicon or tungsten or magnetron)	USPAT	OR	ON	2005/03/18 08:47
S52	34	"5616208" and (plasma)	USPAT	OR	ON	2005/03/18 08:47
S53	3	"6444042" and (microwave or magnetron silicon or tungsten)	USPAT	OR	ON	2005/03/18 08:49
S54	3963	plasma near15 (microwave and electrode)	US-PGPUB; USPAT; USOCR; EPO; JPO; DERWENT; IBM_TDB	OR	ON	2005/03/18 08:50
S55	2288	plasma near15 (microwave and electrode)	USPAT	OR	ON	2005/03/18 08:50
S56	2	(plasma near15 (microwave and electrode)) same (silicon and tungsten)	USPAT	OR	ON	2005/03/18 08:50
S57	3	((nozzle or shower) near10 (heater or heating or heater)) and microwave and ((cooling near5 (medium or fluid)) near15 (shower or nozzle)) and ("cvd" or "chemical vapor deposition")	US-PGPUB; USPAT; USOCR; EPO; JPO; DERWENT; IBM_TDB	OR	ON	2005/03/18 09:03
S58	3	((nozzle or shower) near10 (heater or heating or heater)) and (microwave or mangnetron) and ((cooling near5 (medium or fluid)) near15 (shower or nozzle)) and ("cvd" or "chemical vapor deposition")	US-PGPUB; USPAT; USOCR; EPO; JPO; DERWENT; IBM_TDB	OR	ON	2005/03/18 09:03
S59	3	((nozzle or shower or spout or jet or sprinkler) near10 (heater or heating or heater)) and (microwave or mangnetron) and ((cooling near5 (medium or fluid)) near15 (shower or nozzle)) and ("cvd" or "chemical vapor deposition")	US-PGPUB; USPAT; USOCR; EPO; JPO; DERWENT; IBM_TDB	OR	ON	2005/03/18 09:04

S60	3	((nozzle or shower or spout or jet or sprinkler) near10 (heater or heating or heater)) and (microwave or mangnetron) and ((cooling near5 (medium or fluid)) near15 (shower or nozzle)) and ("cvd" or (chemical near5 vapor near5 deposition))	US-PGPUB; USPAT; USOCR; EPO; JPO; DERWENT; IBM_TDB	OR	ON	2005/03/18 09:04
S61	5	((nozzle or shower or spout or jet or sprinkler) near10 (heater or heating or heater)) and (microwave or mangnetron) and ((cooling near5 (medium or fluid)) near15 (shower or nozzle or spout or jet or sprinkler)) and ("cvd" or (chemical near5 vapor near5 deposition))	US-PGPUB; USPAT; USOCR; EPO; JPO; DERWENT; IBM_TDB	OR	ON	2005/03/18 09:17
S62	0	"6576481" and microwave	US-PGPUB; USPAT; USOCR; EPO; JPO; DERWENT; IBM_TDB	OR	ON	2005/03/18 15:12
S63	0	"6576481" and (microwave or magnetron)	US-PGPUB; USPAT; USOCR; EPO; JPO; DERWENT; IBM_TDB	OR	ON	2005/03/18 15:14
S64	1	"6841203" and (microwave or magnetron)	USPAT	OR	ON	2005/03/18 15:28
S65	12	"5647945" and fluor$7	US-PGPUB; USPAT; USOCR; EPO; JPO; DERWENT; IBM_TDB	OR	ON	2005/03/18 15:31
S66	12	"5647945" and $5fluor$7	US-PGPUB; USPAT; USOCR; EPO; JPO; DERWENT; IBM_TDB	OR	ON	2005/03/18 15:31
S67	13	"5647945" and (silicon or tungsten)	USPAT	OR	ON	2005/03/18 15:53
S68	3	"5647945" and (silicon and tungsten)	USPAT	OR	ON	2005/03/18 16:14
S69	2	("6841203" or "6645303") and frequency	USPAT	OR	ON	2005/03/18 16:16
S70	2	("6841203" or "6645303") and (frequency near20 microwave)	USPAT	OR	ON	2005/03/18 16:16